



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Tabuchi, T., et al.
Appl. No.: 09/730,813
Conf. No.: 9116
Filed: December 6, 2000
Title: SURFACE TREATMENT APPARATUS
Art Unit: 1763
Examiner: Parviz Hassanzadeh
Docket No.: 0112780-00017

Commissioner for Patents
Washington, DC 20231

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RESPONSE TO OFFICE ACTION

Sir:

This Response is submitted in response to the non-Final Office Action mailed September 25, 2002. Applicants request amendment and reconsideration of the patent application.

In the Specification:

Please amend the specification at page 15, lines 8-11 to read as follows.

When a number of the plasma nozzles are to be disposed, hollow discharge generated at all of these nozzles is preferable, as it allows to form a uniform thin film at a high speed even for a large area substrate.

In the Claims:

Please amend claims 1, 4, 5, and 19 to read as follows:

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1. (Amended) A surface treatment apparatus for making raw material gas plasma by generating plasma, in a casing provided with plasma generation means, a raw material gas inlet and a substrate support table, by the plasma generation means and giving plasma treatment to the surface of a substrate placed on said substrate support table, wherein: